Form PTO-1449 (REV. 1/06)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 126821		APPLICATION NO. 10/565,968					
INFORMATION DISCLOSURE STATEMENT											
(Use several sheets if necessary)					APPLICANT(S) Satoshi TAKEI et al.						
					DATE 31, 2006		GROUP				
FOREIGN PATENT DOCUMENTS											
Examiner Initials	Cite No.	Document Number	Date		Country		With English Abstract	With English Translation			
PAR	1.	JP-A-2000-294504	10-2000		Japan		х	x			
	2.	JP-A-2002-47430	02-2002		Japan		х	x			
	3.	JP-A-2002-190519	07-2002		Japan		х	х			
	4.	WO 02/05035	01-2002		WIPO		х				
	5.	JP-A-2002-128847	05-2002		Japan		х	x			
	6.	JP-A-2001-192411	07-2001		Japan		х	x			
	7.	JP-A-2000-264921	09-2000		Japan		х	х			
	8.	JP-A-07-316268	12-1995	· · · · · ·	Japan		х	х			
	9.	JP-A-2002-105137	04-2002		Japan		х	х			
	10.	JP-A-10-221855	08-1998		Japan		x	х			
	. 11.	JP-A-2002-97231	04-2002		Japan		x	х			
	12.	JP-A-2002-80537	03-2002		Japan		x	х			
CVA	13.	JP-A-2002-72488	03-2002		Japan		х	х			
-											
	·		OTHER D	OCUMEN	NTS						
Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)									
111	14.	Lynch, Tom et al., "Properties and Performance of Near UV Reflectivity Control Layers", US, in Advances in Resist Technology									
RVA.		and Proceedings XI, Omkaram Nalamasu et., Proceedings of SPIE, 1994, Vol. 2195, pp. 225-229									
11	15.	Taylor, G. et al., "Methacrylate Resists	and Antire	flective C	oatings for 193 nm Lithography	/", US, in M	icrolithograph	y 1999: in			
1.A		Advances in Resist Technology and Pro	ocessing X	VI, Will C	Conley ed., Proceedings of SPIE	E, 1999, Vol.	. 3678, pp. 17	4-185			
WA	16.	Meador, Jim D. et al., "Recent Progress in 193 nm Antireflective Coatings", US in Microlithography 1999: in Advances in Resist									
		Technology and Processing XVI, Will Conley ed., Proceedings of SPIE, 1999, Vol 3678, pp. 800-809									
EXAMINER	P.,	Ashton DATE CONSIDERED 3-28-07									
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.											

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					FILING DATE GROUP January 31, 2006							
U.S. PATENT DOCUMENTS												
Examiner Initials	Cite No.	Document Number	Date		Name							
RAI	17.	5,919,599	07-1999		Meador et al.							
	18.	5,693,691	12-1997		Flaim et al.							
	19.	6,686,124 B1	02-2004		Angelopoulos et al.		,					
	20.	2002/0093069 A1	07-2002		Hong et al.							
	21.	2002/0127789 A1	09-2002		Hong et al.			-				
	22.	2002/0090452 A1	07-2002		Hong et al.							
RA	23.	2002/0123586 A1	09-2002		Hong et al.							
		FORE	IGN PAT	ENT DOO	UMENTS		*****					
Examiner Initials	Cite No.	Document Number	Date		Country		With English Abstract	With English Translation				
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